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**1 Super-resolution enhancement method with phase-shifting mask available for random patterns**

Misaka, A.; Matsuo, T.; Sasago, M.;

VLSI Technology, 2002. Digest of Technical Papers. 2002 Symposium on , 11-13 June 2002

Pages:200 - 201

[\[Abstract\]](#)   [\[PDF Full-Text \(364 KB\)\]](#)   IEEE CNF

**2 Binary and phase shifting mask design for optical lithography**

Liu, Y.; Zakhor, A.;

Semiconductor Manufacturing, IEEE Transactions on , Volume: 5 , Issue: 2 , May 1992

Pages:138 - 152

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**3 Amplitude-phase-shift masks for projection lithography of submicron technology**

Novosyadlyy, S.;

CAD Systems in Microelectronics, 2003. CADSM 2003. Proceedings of the 7th International Conference. The Experience of Designing and Application of , 18-22 Feb. 2003

Pages:66 - 68

[\[Abstract\]](#)   [\[PDF Full-Text \(319 KB\)\]](#)   IEEE CNF

**4 Investigation of half-tone phase shift mask with FIB and blue laser repair**

Sang-Man Bae; Do-Hwa Lee; Hee-Mok Lee; Myung-Goon Gill; Bong-Ho Kim; Dong-Jun Ahn;

VLSI and CAD, 1999. ICVC '99. 6th International Conference on , 26-27 Oct. 1999  
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### SNP Applications / Characterizing Phase Shift Masks - Surface ...

SNP 9000 Applications. Characterizing **Phase Shift Masks**, Photomask

Applications. Both embedded (EPSM) and alternating (APSM) present ...

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### SNP Applications - Surface/Interface, Inc.

... **Mask Repair Mask Repair**, Binary Chrome on Glass (COG), Embedded **Phase Shift** (EPSM) and Alternating **Phase Shift** photomasks (APSM) all require repair... ..

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### iN-Phase: Phase shift mask

... Automatic shifter adjustment to prevent **phase conflict**; MRC and litho-aware placement ensures **mask** manufacturability; Integrated **phase-shifting** design rule ...

[www.synopsys.com/products/ntimrg/inphase\\_ds.html](http://www.synopsys.com/products/ntimrg/inphase_ds.html) - 12k - [Cached](#) - [Similar pages](#)

### Synopsys Products - Phase Shifting

... operates on a fundamentally different principle from that used for conventional lithography, by using ordinary chrome on glass **masks** to **phase-shift** the light ...

[www.synopsys.com/products/ntimrg/phase\\_shift\\_ds.html](http://www.synopsys.com/products/ntimrg/phase_shift_ds.html) - 8k - [Cached](#) - [Similar pages](#)

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### TechOnLine - Alternatives to Alternating Phase Shift Masks for ...

Alternatives to Alternating **Phase Shift Masks** for 65nm J. Andres Torres

and Wilhelm Maurer Mentor Graphics White Paper. 193nm lithography ...

[www.techonline.com/community/tech\\_group/soc/tech\\_paper/29905](http://www.techonline.com/community/tech_group/soc/tech_paper/29905) - 29k - [Cached](#) - [Similar pages](#)

### TechOnLine - (Sub-) 100nm Gate Patterning Using 248nm Alternating ...

... In this way the initial 0.15 $\mu$ m design was split up in a dark-field

**phase-shifting mask** and a binary trim **mask**. On the **phase-shifting** ...

[www.techonline.com/community/tech\\_group/eda/tech\\_paper/29541](http://www.techonline.com/community/tech_group/eda/tech_paper/29541) - 29k - [Cached](#) - [Similar pages](#)

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### Lasertec News Release "Phase Shift Mask Measurement System for F2 ...

New Product, "**Phase Shift Mask Measurement System for F2 Lithography**".

Overview. Lasertec Corporation has received an order for MPM157 ...

[www.lasertec.co.jp/hotnews/MPM157/e-MPM157.html](http://www.lasertec.co.jp/hotnews/MPM157/e-MPM157.html) - 15k - [Cached](#) - [Similar pages](#)

### Lasertec News Release APSM Etching Monitor " QSM400 "

... First and newly introduced in the market, A Monitor for controlling the depth of etching on **phase shift** pattern for Levenson type **phase shift mask** production. ...

[www.lasertec.co.jp/hotnews/QSM400/e-QSM400.html](http://www.lasertec.co.jp/hotnews/QSM400/e-QSM400.html) - 16k - [Cached](#) - [Similar pages](#)

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of material featuring desired refractive index and thickness is locally added ...

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